

**GANPAT UNIVERSITY****B. Tech. Semester VII Electronics and Communication Engineering****CBCS Regular Examination December-2013****2EC703 VLSI TECHNOLOGY****Time: 3 Hours****Total Marks: 70****Instructions:**

1. Attempt all questions.
2. Answers to the two sections must be written in separate answer books.
3. Figures to the right indicate full marks.
4. Use following data.

$$\Phi_{F(\text{gate})} = 0.55\text{V}, kT/q = 0.026\text{V}, q = 1.6 \times 10^{-19}\text{C}, \epsilon_0 = 8.85 \times 10^{-14}\text{F/cm},$$

$$\epsilon_{\text{Si}} = 11.7 \times \epsilon_0\text{F/cm}, \epsilon_{\text{ox}} = 3.7 \times \epsilon_0\text{F/cm}, n_i = 1.45 \times 10^{10}/\text{cm}^3$$

**SECTION-I**

- 1 (A) Draw schematic and optimize stick diagram layout for following : 6
- (1)  $Y = (A(D+E) + BC)'$
  - (2) 4 input NAND gate
- (B) Draw the following digital circuit using transmission gate : 6
- (1) 4:1 MUX using 2:1 MUX
  - (2)  $F = AB + A'C' + AB'C$
- OR**
- 1 (A) Draw the following CMOS based circuit : 6
- (1) CMOS SR latch based on NOR2
  - (2) CMOS AOI realization of the JK latch
- (B) Draw the following digital circuit using Complementary Pass transistor logic : 6
- (1) 2 input AND and NAND gate
  - (2) Full adder
- 2 (A) Draw the circuit diagram of a TSPC based rising edge-triggered DFF. 5
- (B) Using NORA implement the function  $AB + (C+D) + (EF+G)$ . 6
- OR**
- 2 (A) Draw 4 stage carry look ahead adder using multiple output domino CMOS gate. 5
- (B) Explain the concept of charge sharing and explain the method of how to remove it. 3
- (C) Implement  $(A+B)C$  using cascade domino CMOS logic. 3
- 3 (A) Write a short note on CMOS ring oscillator 6
- (B) Which are the two different VLSI design styles? How these design styles affect the design cycle time and circuit performance? Explain. 6

## SECTION-II

- 4 (A) Write a short note on short channel effect. 6  
(B) Explain MOSFET operation in linear and saturation with suitable diagram. 6
- OR**
- 4 (A) Write a short note on 6  
(1) Narrow channel effect  
(2) Constant field scaling
- (B) Calculate the threshold voltage  $V_{TO}$  at  $V_{SB}=0$ , for a polysilicon gate n-channel MOS transistor, with the following parameter: Substrate doping density  $N_A=10^{16} \text{ cm}^{-3}$  polysilicon gate doping density  $N_D = 2 \times 10^{20} \text{ cm}^{-3}$ , gate oxide thickness  $t_{ox}=500\text{\AA}$ , and oxide-interface fixed charge density  $N_{OX} = 4 \times 10^{10} \text{ cm}^{-2}$  6
- 5 (A) What is noise margin ? Define  $V_{IH}, V_{IL}, V_{OL}, V_{OH}, V_{TH}$ . 6  
(B) Draw voltage transfer characteristics of CMOS inverter, identify critical voltage points and Find expressions of  $V_{IL}$ . 5
- OR**
- 5 (A) Draw voltage transfer characteristics of resistive load inverter, identify critical voltage points and Find expressions of  $V_{OL}$ . 6  
(B) Consider the following for inverter design problem : 5  
Given:  $V_{DD}=5\text{V}, k_n' = 30\mu\text{A/V}^2$  and  $V_{TO,n}=1.0\text{V}$ ,  
Find the value of  $R_L$  if  $W/L$  ratio is 2 and  $V_{OL}=0.2\text{V}$ .
- 6 (A) Explain working principle of CMOS SRAM cell with necessary circuit diagram and waveforms for read and write operation. 6  
(B) Explain in detail latch-up. 6

**End of Paper**